

**DRIP MANIFOLD FOR UNIFORM CHEMICAL DELIVERY**  
**ABSTRACT OF THE DISCLOSURE**

A method for cleaning a wafer with a drip nozzle being configured for use in a  
5 drip manifold that is oriented over a brush of a wafer cleaning system is provided. The  
drip nozzle has a first end and a second end with a passage defined there between where  
the passage includes a wall that extends longitudinally between the first end and the  
second end. An orifice is defined within the passage and located at the first end of the  
drip nozzle. The method includes inputting a fluid into the drip nozzle at an acute angle  
10 relative to a longitudinal extension of the wall and reflecting the fluid stream off an  
internal wall of the drip nozzle at least twice in a direction that is toward the second end.  
The method further includes outputting at least one substantially uniform drop from the  
second end of the passage.